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 Sheet 1
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FORM PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	004066/CONS/MBE Attorney Docket No.:	Serial No.: 09/88,966
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use Several Sheets If Necessary)		Applicant: Arackaparambil et al.	
(37 CFR § 1.98(b))		Filing Date: 07/29/99	Group: 2788 2121

U.S. PATENT DOCUMENTS

Examiner Initials		Serial/Patent Number	Issue Date	Applicant/Patentee	Class	Subclass	Filing Date
SND	AA	5,910,011	6/8/99	Cruse	438	16	5/12/97
SND	AB	5,754,297	5/19/98	Nulman	356	381	4/14/97
SND	AC	5,698,989	12/16/97	Nulman	324	719	9/13/96
SND	AD	5,398,336	3/14/95	Tantry et al.	395	600	7/16/93
SND	AE	5,367,624	11/22/94	Cooper	395	157	6/11/93
SND	AF	5,295,242	3/15/94	Mashruwala et al.	395	159	11/2/90
SND	AG	5,236,868	8/17/93	Nulman	437	190	4/20/90
SND	AH	5,108,570	4/28/92	Wang	204	192.3	3/30/90

FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

		Document Number	Publication Date	Country / Patent Office	Class	Subclass	Translation Yes	No

OTHER DOCUMENTS (including Author, Title, Date, Relevant Pages, Place of Publication)

SND	AI	W.R. Runyan et al. <u>Semiconductor Integrated Circuit Processing Technology</u> , Addison-Wesley Publ. Comp. Inc., p.48, 1994						
SND	AJ	Peter van Zandt, <u>Microchip Fabrication</u> , 3 rd ed., McGraw-Hill, pp. 472-478, 1997						
SND	AK	R. Zorich, <u>Handbook Of Quality Integrated Circuit Manufacturing</u> , Academic Press Inc., pp. 464-498, 1991.						
SND	AL	SEMI E10-96, <u>Standard For Definition And Measurement Of Equipment Reliability, Availability And Maintainability (RAM)</u> , published by Semiconductor Equipment and Materials International (SEMI), pp. 1-23, 1996						

Examiner:

Harker

Date Considered:

3/21/02

EXAMINER:

Initial citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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PATENT & TRADEMARK OFFICE

Serial No.: 09/363,966

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FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION

OTHER DOCUMENTS (including Author, Title, Date, Relevant Pages, Place of Publication)

Date Considered: 3/21/02

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Sheet 1 of 1

FORM PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	004066/CONS/MBE Attorney Docket No.:	Serial No.: 09,363,966
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(37 CFR § 1.98(b))		Filing Date: 7/29/99	Group: 2786 2121

U.S. PATENT DOCUMENTS							
Examiner Initials		Serial/Patent Number	Issue Date	Applicant/Patentee	Class	Subclass	Filing Date
SMB	AA	6,054,379	4/25/00	Yau et al.	438	623	2/11/98
SMB	AB	5,808,303	9/15/98	Schlagheck et al.	250	330	1/29/97
SMB	AC	5,629,216	5/13/97	Wijaranakula et al.	438	502	2/27/96
SMB	AD	5,410,473	4/25/95	Kaneko et al.	364	413.06	12/16/92

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FOREIGN PATENT OR PUBLISHED FOREIGN PATENT APPLICATION								
		Document Number	Publication Date	Country / Patent Office	Class	Subclass	Translation Yes	No
SMB	AE	HEI 11-67853	1999	Japan, Kokai Patent Application	/	/	X	
SMB	AF	HEI 1-283934	1989	Japan, Kokai Patent Application	/	/	X	

OTHER DOCUMENTS (including Author, Title, Date, Relevant Pages, Place of Publication)		

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Examiner: <i>M. S. S.</i>	Date Considered: 3/21/02
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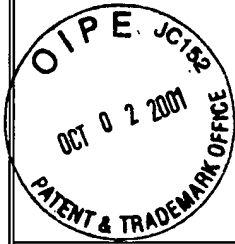
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U.S. PATENT DOCUMENTS

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INFORMATION DISCLOSURE CITATION IN AN APPLICATION

(PTO-1449)


 ATTY. DOCKET NO.
4066/Consilium/MBE

 SERIAL NO.
09/363,966

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OCT 0 4 2001

 APPLICANT
John F. ARACKAPARAMBIL et al.

Technology Center 2100

 FILING DATE
July 29, 1999

 GROUP
2786 2121

U.S. PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
snb	4,796,194	01/03/89	Atherton	364	468	08/20/86
snb	5,089,970	02/18/92	Lee et al.	364	468	10/05/89
snb	5,309,221	05/03/94	Fischer et al.	356	355	12/31/91
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snb	5,490,097	02/06/96	Swenson et al.	364	578	08/06/93
snb	5,661,669	08/26/97	Mozumder et al.	364	552	06/07/95
snb	5,751,582	05/12/98	Saxena et al.	364	468.16	09/24/96
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EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No

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	Dishon, G., D. Eylon, M. Finarov, and A. Shulman. "Dielectric CMP Advanced Process Control Based on Integrated Monitoring." Ltd. Rehovot, Israel: Nova Measuring Instruments.
snb	Moyne, James R., Nauman Chaudhry, and Roland Telfeyan. 1995. "Adaptive Extensions to a Multi-Branch Run-to-Run Controller for Plasma Etching." <i>Journal of Vacuum Science and Technology</i> . Ann Arbor, Michigan: University of Michigan Display Technology Manufacturing Center, pp 1-12, 1995
snb	Moyne, James, Roland Telfeyan, Arnon Hurwitz, and John Taylor. August 1995. "A Process-Independent Run-to-Run Controller and Its Application to Chemical-Mechanical Planarization." <i>SEMI/IEEE Advanced Semiconductor Manufacturing Conference and Workshop</i> . Ann Arbor, Michigan: The University of Michigan, Electrical Engineering & Computer Science Center for Display Technology & Manufacturing, pp 1-2, 8/15/95
snb	Dishon, G., M. Finarov, R. Kipper, J.W. Curry, T. Schraub, D. Trojan, 4 th Stambaugh, Y. Li and J. Ben-Jacob. February 1996. "On-Line Integrated Metrology for CMP Processing." Santa Clara, California: VMIC Speciality Conferences, 1 st International CMP Planarization Conference, pp 1-6, 2/96
snb	Campbell, W. Jarrett, and Anthony J. Toprac. February 11-12, 1998. "Run-to-Run Control in Microelectronics Manufacturing." Advanced Micro Devices, TWMCC, pp 1-15, 2/11/98


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Garland

DATE CONSIDERED

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EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to Applicant.

INFORMATION DISCLOSURE CITATION IN AN APPLICATION  (PTO-1449)	ATTY. DOCKET NO. 4066/Consilium/MBE	SERIAL NO. 09/363,966
	RECEIVED OCT 04 2001	
	APPLICANT John F. ARACKAPARAMBIL et al. Technology Center 2100	
	FILING DATE July 29, 1999	GROUP 2786 2121

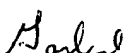
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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE

FOREIGN PATENT DOCUMENTS

EXAMINER'S INITIALS	PATENT NO.	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
						Yes	No

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EXAMINER 	DATE CONSIDERED 3/21/02

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